What Is Claimed Is:

1. An etchant fume exhaust apparatus installed inside an etching system, the etchant fume exhaust apparatus comprising:

an exhaust hole that provides a passage to discharge gaseous etchant generated in the etching system;

an exhaust plate disposed to collect liquefied etchant from the exhaust hole;

a support part that fixes the exhaust plate to the exhaust hole; and

an exhaust line connected with the exhaust plate and through which the liquefied etchant in the exhaust plate is removed from the exhaust plate.

2. The etchant fume exhaust apparatus of claim 1, wherein the exhaust hole has a hollow cylindrical shape.

3. The etchant fume exhaust apparatus of claim 1, wherein an upper surface of the exhaust plate is formed such that a width of an opening formed by a first end of the upper surface most proximate to the exhaust hole is larger than a width of an opening formed by a second end of the upper surface most distal from the exhaust hole.

4. The etchant fume exhaust apparatus of claim 3, wherein a slope of the upper surface of the exhaust plate is constant between the first and second ends of the upper surface.

5. The etchant fume exhaust apparatus of claim 1, wherein a space between the exhaust hole and the exhaust plate provides a route through which the gaseous etchant generated in the etching system is induced into the exhaust hole.

6. The etchant fume exhaust apparatus of claim 1, wherein the support part is formed in a substantially frustoconical shape in which a width of the support part most proximate to the exhaust hole is smaller than a width of the support part most distal from the exhaust hole.

7. The etchant fume exhaust apparatus of claim 1, wherein the exhaust line is disposed such that liquefied etchant in the exhaust line is removed from the exhaust apparatus.

8. The etchant fume exhaust apparatus of claim 1, wherein the exhaust line is disposed such that liquefied etchant in the exhaust line is reused the etching system.

9. An etching system comprising:

an etchant supply apparatus that supplies etchant;

an etchant fume exhaust apparatus disposed in an upper portion of the etchant supply apparatus, the etchant fume exhaust apparatus comprising an exhaust hole that provides a passage to discharge gaseous etchant, an exhaust plate disposed to collect the gaseous etchant that has condensed into a liquefied etchant and that is dripping from the exhaust hole, a support part that fixes the exhaust plate to the exhaust hole, and an exhaust line connected to the exhaust plate and removes the liquefied etchant collected in the exhaust plate; and

a chamber in which etching occurs using the etchant supplied from the etchant supply apparatus.

10. The etching system of claim 9, wherein the exhaust hole has a hollow cylindrical shape.

11. The etching system of claim 9, wherein an upper surface of the exhaust plate is formed such that a width of an opening formed by a first end of the upper surface most proximate to the exhaust hole is larger than a width of an opening formed by a second end of the upper surface most distal from the exhaust hole.

12. The etching system of claim 9, wherein a slope of the upper surface of the exhaust plate is constant between the first and second ends of the upper surface.

13. The etchant fume exhaust apparatus of claim 9, wherein a space between the exhaust hole and the exhaust plate provides a route through which the gaseous etchant generated in the etching system is induced into the exhaust hole.

14. The etchant fume exhaust apparatus of claim 9, wherein the support part is formed in a substantially frustoconical shape in which a width of the support part most proximate to the exhaust hole is smaller than a width of the support part most distal from the exhaust hole.

15. The etchant fume exhaust apparatus of claim 9, wherein the exhaust line is disposed such that the liquefied etchant in the exhaust line is removed from the exhaust apparatus.

16. The etchant fume exhaust apparatus of claim 9, wherein the exhaust line is disposed such that the liquefied etchant in the exhaust line is reused the etching system.

17. A method of decreasing contact between condensed etchant in an etchant fume exhaust apparatus and equipment in an etching system, the method comprising:

providing a passage through which gaseous etchant generated in the etching system is discharged and in which the gaseous etchant condenses into the condensed etchant; and

collecting the condensed etchant escaping from the passage in a collection site prior to contact occurring between the condensed etchant and the equipment, thereby inhibiting the condensed etchant from contacting the equipment.

18. The method of claim 17, further comprising removing the condensed etchant from the collection site.

19. The method of claim 17, further comprising tapering an inner surface of the collection site such that condensed etchant that rebounds after striking the inner surface is directed at an oblique angle with respect to the condensed etchant striking the inner surface.

20. The method of claim 19, further comprising tapering a majority of the inner surface such that the majority of the inner surface has a constant slope.

21. The method of claim 17, further comprising inducing the gaseous etchant into a space between the passage and the collection site.

22. The method of claim 17, further comprising intercepting at least a portion of the condensed etchant from the passage traveling towards the collection site before the condensed etchant contacts the collection site.

23. The method of claim 22, further comprising increasing an amount of intercepted condensed etchant by tapering an interceptor that intercepts the portion of the condensed etchant such that the interceptor widens with increasing distance from the passage.

24. The method of claim 18, further comprising removing the collected condensed etchant from the exhaust apparatus.

25. The method of claim 18, further comprising reusing the collected condensed etchant in the etching system.